

Special Issue

Application of Plasma Technology for Nanomodeling and Nanofabrication

Message from the Guest Editors

Plasma technology has emerged as a transformative tool in nanofabrication and nanomodeling, enabling precise control over materials and the construction of intricate nanostructures. Plasmas, made up of charged particles, ions, and neutral atoms, drive processes such as etching, deposition, surface modification, and ion implantation. These processes are essential for creating nanoscale features and tailored material surfaces, establishing plasma techniques as indispensable for advances in electronics, photonics, and energy devices.

Researchers are encouraged to submit original articles, reviews, and perspectives that contribute to the evolving field of plasma-based nanotechnology.

Guest Editors

Prof. Dr. William Chiappim Junior

Laboratory of Plasmas and Applications, Department of Physics, School of Engineering and Sciences, São Paulo State University (UNESP), Guaratinguetá 12516-410, SP, Brazil

Dr. Felipe de Souza Miranda

Plasmas and Process Laboratory, Department of Physics, Aeronautics Institute Technology, São José dos Campos 12228-900, Brazil

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Editorial Office
MDPI, Grosspeteranlage 5
4052 Basel, Switzerland
Tel: +41 61 683 77 34
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Editor-in-Chief

Prof. Dr. Giancarlo Cravotto

Department of Drug Science and Technology, University of Turin, Via P. Giuria 9, 10125 Turin, Italy

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